
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT

In re application of: PATRICK et al.

Attorney Docket No.:
LAM1P061/P0318

Application No.: 08/925,985

Examiner: MARKOFF, A.

Filed: September 9, 1997

Group: 1746

Title: APPARATUS FOR IMPROVING ETCH
UNIFORMITY AND METHODS
THEREFOR

CERTIFICATE OF EXPRESS MAILING

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Signed: _____

Alison Gates

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated December 5, 2001, please amend the above-identified patent application as follows:

In the Claims:

Please amend claims 9 and 30.

All pending claims have been reproduced below for the convenience of the Examiner. Claims which have been changed by this amendment are indicated with an asterisk ("*").

1. (Thrice Amended) In a plasma processing chamber, a method for improving etch uniformity while etching a semiconductor substrate, comprising:

placing said semiconductor substrate into a sacrificial substrate holder, said sacrificial substrate holder being configured to present a sacrificial etch portion surrounding said semiconductor substrate to a plasma within said plasma processing chamber to permit said